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The ion energy distributions and ion flux composition from a high power impulse magnetron sputtering discharge

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#	Paper	IF	Citations
261	Highly ionized fluxes of sputtered titanium atoms in high-power pulsed magnetron discharges. <i>Plasma Sources Science and Technology</i> , 2008 , 17, 025010	3.5	52
260	Ion composition produced by high power impulse magnetron sputtering discharges near the substrate. <i>Journal of Applied Physics</i> , 2008 , 104, 083305	2.5	55
259	Sputtering in vacuum: A technology for ultraclean metallization and space propulsion. 2008 ,		
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256	Origins of ion energy distribution function (IEDF) in high power impulse magnetron sputtering (HIPIMS) plasma discharge. <i>Journal Physics D: Applied Physics</i> , 2008 , 41, 095203	3	76
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